

# **IKONICS Announces New RapidMask Film**

July 21 2004

---

IKONICS Corporation, a Duluth based imaging technology company, announced today the introduction of a new product to its successful RapidMask(TM) line of photoresist films. RapidMask(TM) High Tack opens up new markets to IKONICS and its customers because it allows a deep etch on glass and other materials.

"RapidMask(TM) High Tack opens up potentially significant new opportunities in signage and architecture, as well as addressing the deep etch needs of a portion of our existing awards market," said Bill Ulland, IKONICS' CEO. "Although RapidMask(TM) is much easier to use than other photoresist films, the shallow etch limitations of the original RapidMask(TM) film has limited the product's use in some markets. New RapidMask(TM) High Tack changes that."

Since IKONICS acquired the RapidMask(TM) technology from DuPont in 2002, the product has been substantially re-engineered to make it more user-friendly and lower the cost. RapidMask(TM) High Definition, introduced in 2003, opened up new markets where fine detail and halftone etching are important; now RapidMask(TM) High Tack expands the capabilities of this unique technology to markets requiring a deeper etch.

IKONICS stock is listed on the Nasdaq SmallCap market under the symbol IKNX.

This press release contains forward-looking statements regarding sales, earnings, and new products that involve risks and uncertainties. The

company's actual results could differ materially as a result of domestic and global economic conditions, competitive market conditions, acceptance of new products, the ability to identify and make suitable acquisitions, as well as the factors described in the company's Form 10-KSB on file with the SEC.

Source: IKONICS Corporation

Citation: IKONICS Announces New RapidMask Film (2004, July 21) retrieved 18 April 2024 from <https://phys.org/news/2004-07-ikonics-rapidmask.html>

This document is subject to copyright. Apart from any fair dealing for the purpose of private study or research, no part may be reproduced without the written permission. The content is provided for information purposes only.